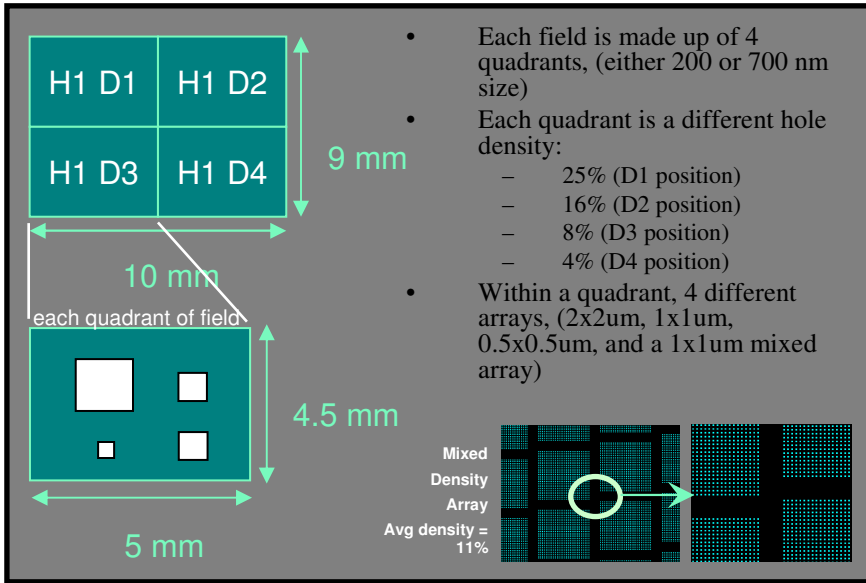


# SKW Associates, Inc,

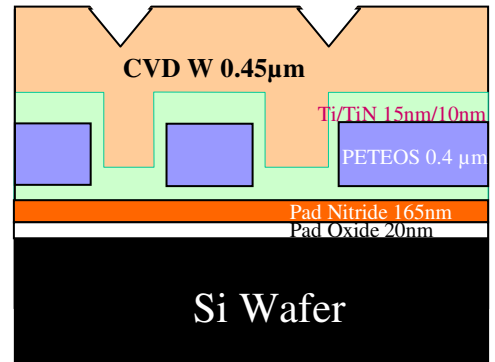
2920 Scott Blvd.  
 Santa Clara, CA 95054  
 Phone (408) 919-0094  
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# SKW 5-RSAX W Plug Patterned Wafer Specifications

Rev. DATE: Jul 30, 2005



SKW 5-RSAX Mask Floor Plan



Cross Sectional View

PARAMETER	NOMINAL	TOLERANCE
Patterning		
Die Size: X	10 mm	+/- 10 µm
Die Size: Y	9 mm	+/- 10 µm

PARAMETER	NOMINAL	TOLERANCE
Pad Oxide thickness		
Lot-to-Lot	200 Å	+/- 5 %
Within-Lot (Wafer-to-Wafer)		+/- 5 %
Within-Wafer		+/- 3 %
Within-Die		+/- 3 %
Pad Nitride thickness		
Lot-to-Lot	1650 Å	+/- 5 %
Within-Lot (Wafer-to-Wafer)		+/- 5 %
Within-Wafer		+/- 3 %
Within-Die		+/- 3 %
PETEOS thickness		
Lot-to-Lot	4000 Å	+/- 5 %
Within-Lot (Wafer-to-Wafer)		+/- 5 %
Within-Wafer		+/- 3 %
Within-Die		+/- 3 %
SION BARC thickness		
Lot-to-Lot	500 Å	+/- 5 %
Within-Lot (Wafer-to-Wafer)		+/- 5 %
Within-Wafer		+/- 3 %
Within-Die		+/- 3 %
LTO thickness		
Lot-to-Lot	600 Å	+/- 5 %
Within-Lot (Wafer-to-Wafer)		+/- 5 %
Within-Wafer		+/- 3 %
Within-Die		+/- 3 %

Ti thickness		
Lot-to-Lot	150 Å	+/- 5 %
Within-Lot (Wafer-to-Wafer)		+/- 5 %
Within-Wafer		+/- 3 %
Within-Die		+/- 3 %
PVD TiN film thickness		
Lot-to-Lot	100 Å	+/- 5 %
Within-Lot (Wafer-to-Wafer)		+/- 5 %
Within-Wafer		+/- 5 %
Within-Die		+/- 5 %
CVD W film thickness		
Lot-to-Lot	4500 Å	+/- 10 %
Within-Lot (Wafer-to-Wafer)		+/- 10 %
Within-Wafer		+/- 5 %
Within-Die		+/- 5 %